

<b>STD SiO2 5/9/2018</b>	<b>OLD RECIPE</b>
Date	5/9/18
<b>Standard SiO2 Coat</b>	
Coat time, min	10
<b>StandardSiO2 Deposition</b>	
Deposition time, min	10
RF power setup, W	30
Pressure, mTorr	800
<b>Gass flow, sccm</b>	
SiH4	300
N2O	1420
T, C	~300
Thickness, nm	343
Dep.rate, nm/min	34.31
Index at 632.8nm	1.475
Index at 1550nm	1.463
Stress, MPa	-264.06
BHF, nm/min	393
Std. clean, min	20

